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Robertson

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Tomoyuki MATSUYAMA et al.

Group Art Unit: 2851

Application No.: 10/067,344

Examiner: R. Fuller

Filed: February 7, 2002

Docket No.: 105218.01

For: METHOD FOR MANUFACTURING EXPOSURE APPARATUS AND METHOD  
FOR MANUFACTURING MICRO DEVICE

AMENDMENT

Director of the U.S. Patent and Trademark Office  
Washington, D.C. 20231

Sir:

In reply to the November 7, 2002, Office Action, the shortened statutory period for reply being extended by the attached Petition for Extension of Time, please amend the above-identified application as follows:

IN THE CLAIMS:

Please replace claims 1-4, 6-22, 24-56, 58, 60 and 62 as follows:

1. (Twice Amended) A method for manufacturing an exposure apparatus comprising:

a providing step of providing a projection system that projects and exposes an image of a predetermined pattern formed on a reticle to a photosensitive substrate;

a setting step of setting a correction member that corrects residual aberration in said projection system at a predetermined position in an optical path between a reticle setting position where said reticle is set and a substrate setting position where said photosensitive substrate is set; and

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